

Press Release

Tel: 732-355-1600 Fax: 732-355-1608



Nanonex Delivered NX 2600 Tool to University of Cincinnati, Ohio.

Princeton NJ, August. 26, 2010:

Nanonex Corporation, the inventor and world's leading provider in nanoimprint lithography solutions with the longest history, announces the delivery of a Nanonex NX-2600 to Engineering Research Center at University of Cincinnati, OH. Nanonex is proud to support the leading edge research at the University of Cincinnati.

The Nanonex NX-2600 is a full wafer nanoimprinter and photolithography aligner. It is capable of all imprint forms: thermal, photo-curable, embossing and photolithography, with sub-5nm imprinting resolution and sub-1 micrometer alignment accuracy. Based on the Nanonex unique patented Air Cushion Press™ technology, the NX-2600 offers unsurpassed uniformity regardless of backside topology, wafer or mask flatness, or backside contamination. This ACP technology also eliminates lateral shifting between the mask and substrate, which significantly increases mask lifetime.

About Nanonex Corporation

Nanonex is the inventor of NIL, the world's first nanoimprint lithography company, and the world's leading provider of nanoimprint solutions that include

equipment, masks, resists and processes. Nanonex's patented and proprietary NIL solutions and Air-Cushion Press™ can manufacture 3D nanostructures with sub-5 nm resolution, large-area uniformity, accurate overlay alignment, high throughput, and low cost. Nanonex NIL solutions have been adopted by a broad spectrum of applications, such as optical devices, data storage, displays, light emitting diodes, semiconductor ICs, biotech, chemical synthesis, and advanced materials. Nanonex has over 100 customers and an installed base of over 50 tools world-wide. Visit www.nanonex.com for additional information.